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(54) Title: CLEANING BASE AND CLEANING SYSTEM

(54) 发明名称: 一种清洁底座及清洁系统

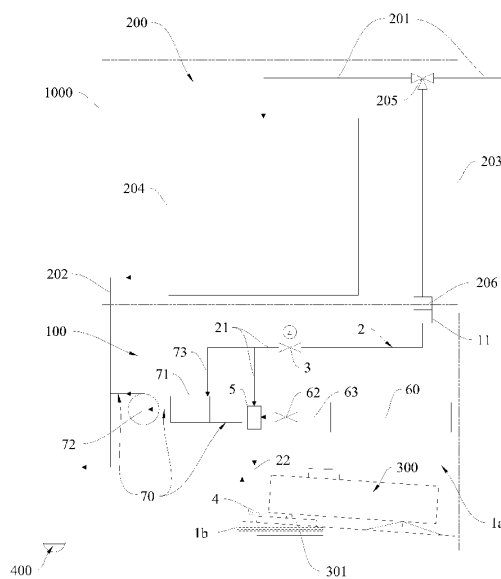


图 6

(57) Abstract: The present application relates to the technical field of laundry treatment, and provides a cleaning base, comprising a bottom frame and a water inlet pipeline. A cleaning portion, and a cleaning cavity for containing a ground cleaning device are formed in the base; the cleaning portion is used for cleaning at least part of the ground cleaning device; the water inlet pipeline is in communicates with the cleaning portion and a tap water source. According to the cleaning base provided by embodiments of the present application, the water inlet pipeline is communicated with the tap water source, so that a water storage structure having a large structural size does

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not need to be provided for the cleaning base, and the overall structural size of the cleaning base is reduced. The tap water source can continuously supply water to a cleaning tank, so that a user does not need to manually add water for the water storage structure, and the automation degree and the operation convenience of a base station are higher.

(57) 摘要: 本申请涉及衣物处理技术领域, 本申请一方面提供一种清洁底座, 包括底框以及进水管路。底座内部形成有清洗部和用于容设地面清洁设备的清洗腔, 所述清洗部用于清洗所述地面清洁设备的至少部分, 进水管路连通所述清洗部和自来水源。本申请实施例提供的清洁底座, 进水管路与自来水源连通, 无需为清洁底座设置结构尺寸大的储水结构, 减少了清洁底座的整体结构尺寸。自来水源可以持续性地向清洗槽供水, 无需用户人工为储水结构加水, 基地的自动化程度和操作便捷性更高。